

REMARKS

Claims 5, 6, 10 and 11 are pending in this application. By this Amendment, claims 5 and 11 are amended. Claims 1-4 and 7-9 are withdrawn due to the finality of the Restriction Requirement.

Applicants thank Examiner Richards for the courtesy extended to Applicant's representative, Mr. Luo, during the July 21, 2005 personal interview. The substance of the personal interview is incorporated in the following remarks.

The Office Action objects to claims 5, 6, 10 and 11. Claims 5 and 11 are amended for better clarity, as discussed during the personal interview. Accordingly, withdrawal of the objection to claims 5, 6, 10 and 11 is respectfully requested.

The Office Action rejects claims 5, 6 and 10 under 35 U.S.C. §103(a) over "Surface-Free Technology by Laser Annealing (SUFTLA)," IEEE, 1999, by Shimoda et al. ("Shimoda I") in view of "Future Trend of TFT Technology," AM-LCD, 2002, by Shimoda ("Shimoda II"); and rejects claim 11 under 35 U.S.C. §103(a) over Shimoda I in view of Applicants' admitted prior art (APA). These rejections are respectfully traversed.

The Office Action asserts that Shimoda I discloses all elements recited in claims 5 and 11 except for forming functional elements using holographic lithography to pattern the functional elements, as recited in claim 5; or forming functional elements using dynamic auto focus to pattern the functional elements, as recited in claim 11. However, the Office Action asserts that Shimoda II and APA respectively supply the subject matter lacking in Shimoda I.

Applicants respectfully submit that Shimoda I, Shimoda II and the APA do not disclose or suggest transferring at least one of the functional elements directly to a second substrate, the second substrate containing a wiring line, the transfer of the at least one of the functional elements including electrically connecting the at least one of the functional elements to the wiring line of the second substrate, as recited in claims 5 and 11.

As discussed during the personal interview, Shimoda I discloses using a transfer substrate to transfer TFTs from an original substrate to a plastic film. See Fig. 2 and the "SUFTLA Process" section of Shimoda I. Shimoda I does not disclose or suggest transferring the TFTs directly from the original substrate to the plastic film, or that the transfer substrate contains a wiring line. Therefore, Shimoda I does not disclose or suggest transferring at least one of the functional elements directly to a second substrate, the second substrate containing a wiring line, the transfer of the at least one of the functional elements including electrically connecting the at least one of the functional elements to the wiring line of the second substrate. Therefore, Shimoda I does not disclose or suggest the subject matter recited in claims 5 and 11.

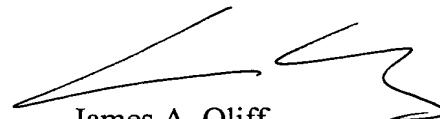
As discussed during the personal interview, Shimoda II discloses a holographic process, and the APA discloses an auto focus process. Shimoda II and the APA do not disclose or suggest transferring at least one of the functional elements directly to a second substrate, the second substrate containing a wiring line, the transfer of the at least one of the functional elements including electrically connecting the at least one of the functional elements to the wiring line of the second substrate, as recited in claims 5 and 11. Therefore, Shimoda II and the APA do not supply the subject matter lacking in Shimoda I.

For at least the above reason, Shimoda I, Shimoda II and the APA do not disclose or suggest the subject matter recited in claims 5 and 11, and claims 6 and 10 depending therefrom. Accordingly, withdrawal of the rejections of claims 5, 6, 10 and 11 under 35 U.S.C. §103(a) is respectfully requested.

In view of the foregoing, it is respectfully submitted that this application is in condition for allowance. Favorable reconsideration and prompt allowance of claims 5, 6, 10 and 11 are earnestly solicited.

Should the Examiner believe that anything further would be desirable in order to place this application in even better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number set forth below.

Respectfully submitted,



James A. Oliff
Registration No. 27,075

Gang Luo
Registration No. 50,559

JAO:GL/kzb

Date: August 17, 2005

OLIFF & BERRIDGE, PLC
P.O. Box 19928
Alexandria, Virginia 22320
Telephone: (703) 836-6400

<p>DEPOSIT ACCOUNT USE AUTHORIZATION Please grant any extension necessary for entry; Charge any fee due to our Deposit Account No. 15-0461</p>
